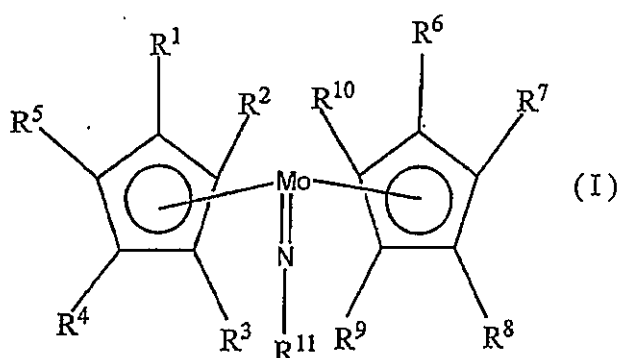


ABSTRACT

In the method of the present invention for producing a thin film, comprising introducing, onto a substrate, a vapor that has been obtained by vaporizing a thin-film-forming material comprising a molybdenum imide compound represented by the following formula (I) and that comprises the molybdenum imide compound; and then forming a thin film comprising molybdenum on the substrate by decomposing and/or chemically reacting the molybdenum imide compound.



(In the formula, R^1 through R^{10} each represent a hydrogen atom or a linear or branched alkyl group having 1 to 5 carbon atoms, and R^{11} represents a linear or branched alkyl group having 1 to 8 carbon atoms.)